

# Cleaning method, cleaning apparatus and electro optical device

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## Abstract of TW278536B

To provide a washing method and a washing apparatus capable of easily removing organic matter adhering to an evaporation mask of a low-molecular organic EL apparatus. The washing apparatus is an apparatus 1 for washing organic matter adhering to the evaporation mask of the low-molecular organic EL apparatus and comprises a first stage 10 for treating the evaporation mask 140 with a pyrrolidone derivative; a second stage 20 for rinsing the evaporation mask 140 with water; a third stage 30 for rinsing the evaporation mask 140 with flowing water; a fourth stage 40 for treating the evaporation mask 140 with ethanol; a fifth stage 50 for drying the evaporation mask 140; and transportation means 5 for successive transporting the evaporation mask 140 to the respective stages. It is preferable to use N-methyl-2-pyrrolidone as the pyrrolidone derivative.

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